					SHEET <u>1</u> OF <u>1</u>		
'Substitute for fo	rm 1449A/PTO			ATTORNEY'S DKT NO.	APPLICATION NO.		
ł				022500-021	10/081,194		
INFO	DRMATH	DISCLO	SURE	APPLICANT Jaroslav BĚLONOŽNÍK			
Ι ςτα	TEMENIT	BYOMPPLIC	TMAC	FILING DATE	GROUP		
] 31/	VICANICIAI	טופאוו בוע	2/141	2/25/02	Unassign d		
	MAY 2						
	(A)	***	S. PATENT	DOCUMENTS			
	U.S. Paris	Decument					
Examiner	Kind Code			Patentee or Applicant	Date of Publication		

	<u> \ \ \ \ \ \ \ \ \ \ \ \ \ \ \ \ \ \ \</u>						_
	37	RIO	U.S. PATENT DOCUMENTS				0.0
	U.S. Parlan	cument					
Examiner Initials	Number	Kind Code (if known)	Name of Patentee or Application of Cited Document	nt	Date of Public (MM-DD-YY		
M	5,218,691	Α	Tuma et al	06/08/1993			
M	5,241,508	Α	Berenguel et al		08/31/19	93	
7111	5,410,680	Α	Challa et al		04/25/19	95	
TILL	5,555,402	Α	Tuma et al		09/10/19	96	_
M	5,781,719	Α	Hirofuji et al RE(JFIV.	CD 07/14/19	98	
97W	5,805,787	Α	Brant et al		09/08/19	98	_
Thy -	5,867,686	Α	Conner et al JUL	262	02/02/19	99	
M	5,987,627	Α	Rawlings, IlTochnolo	- ^	11/16/19	99	_
M	5,991,852	Α	Rawlings, IIITechnolo Bagley	gy Cent	er 2100 11/23/19	99	_
YM.	6,105,103	Α	Courtright, II et al	_	08/15/20	00	_
YNK.	6,336,174	B1	Li et al		01/01/20	02	_
M	6,374,389	B1	Tuma et al		04/16/20	02	
	Foreign Patent		OREIGN PATENT DOCUMENTS	· · · · · · · · · · · · · · · · · · ·		3196	-
Examiner	Foreign Faterit	Kind Code		D	ate of Publication	Translat	tic
Initials	Number	(if known)	Country		(MM-DD-YYYY)	Yes	,
							_
Examiner Initials		name of autho	PATENT LITERATURE DOCUMI or (in CAPITAL LETTERS), title of the ar urnal, serial, symposium, catalog, etc.), publisher, city and/or country where	ticle (whe date, pag	e(s), volume-issue numb	he	1000
	U			1			
xaminer Signature	Josens Cent	U	Date Considered	A	iguist 3,2	004	

EXAMINER: Initial if reference considered, whether or not citation is in conformance with MPEP 609; draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant. SEND TO: Assistant Commissioner for Patents, Washington, D.C. 20231.